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Disentangling Exciton Linewidth Broadening Factors in Transition Metal Dichalcogenide Monolayer with Electron Energy Loss Spectroscopy

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Monolayer two-dimensional transition metal dichalcogenides (TMDs) have invoked great interest for potential applications because of their strong light-matter interactions and direct energy gap. However, the external environment heavily influences the optical properties of TMD monolayers. Encapsulating TMDs in *h*-BN is recognized as the most effective way to preserve their intrinsic optical properties [1,2], and to obtain narrow excitonic linewidths. It has been proven that *h*-BN encapsulation can reduce the roughness of graphene from 114 ± 1 to 12 ± 5 pm [3]. Besides roughness, surface protection [1], charge disorder [2], and variations of dielectric environment [4] are also believed to be key factors that could induce inhomogeneous excitonic linewidth broadening of TMDs. However, no such study has comprehensively compared and disentangled the various proposed factors that contribute to excitonic linewidth broadening exists, because few techniques can address all factors single-handedly.

In order to explore the role of these factors, we investigated the roughness and absorption behavior by electron energy loss spectroscopy (EELS) of WS₂ monolayers either supported or encapsulated by two different nanosheets (*h*-BN and Si₃N₄) in a scanning transmission electron microscope (STEM) [5]. Using this technique, the factors leading to exciton absorption linewidth inhomogeneity can be ranked in increasing order of importance: monolayer roughness, surface cleanliness, and substrate induced charge trapping. In Fig. 1., the EELS spectra of WS₂ monolayers in different configurations are illustrated.

Experiments were done on the ChromaTEM microscope, a modified Nion HERMES 200 equipped with an electron monochromator. The electron beam energy is set at 60 keV with a spread down to below 10 meV. The convergence half-angles for the EELS and diffraction measurements are 10 mrad and 1 mrad. Roughness was measured with the sample tilted with respect to the electron beam from 0 to 385 mrad as shown in Fig. 2, which is similar to previous experiments for graphene [3,6]. Corrugated monolayers are expected to show diffraction spots blurring as the tilt angle increases, whereas a flat monolayer does not. Additionally, numerical calculations for the diffraction patterns under different roughnesses are performed in QSTEM [7] to ascertain the corrugation of the monolayers in each configuration.

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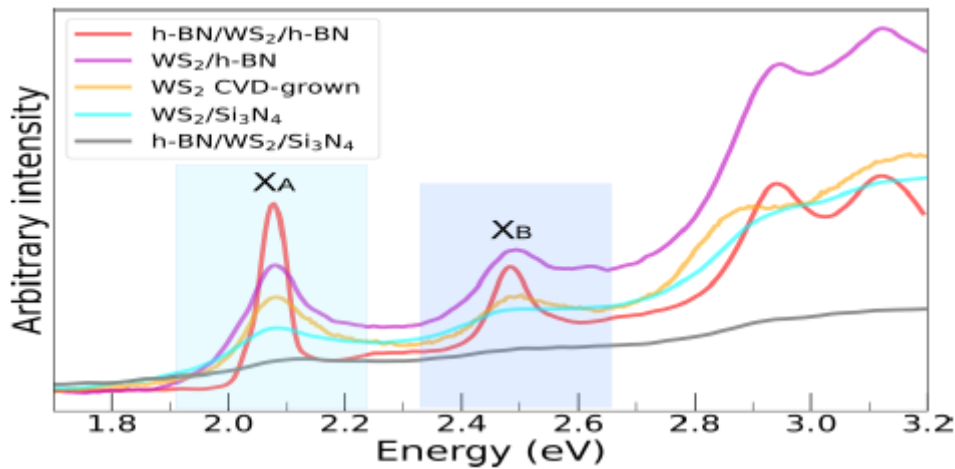


Figure 1. EELS spectra of WS₂ monolayers in various configurations at 110 K. The linewidth of the A exciton increases in order: *h*-BN encapsulated, *h*-BN supported, freestanding CVD-grown, Si₃N₄ supported and Si₃N₄/*h*-BN encapsulated WS₂ monolayers.

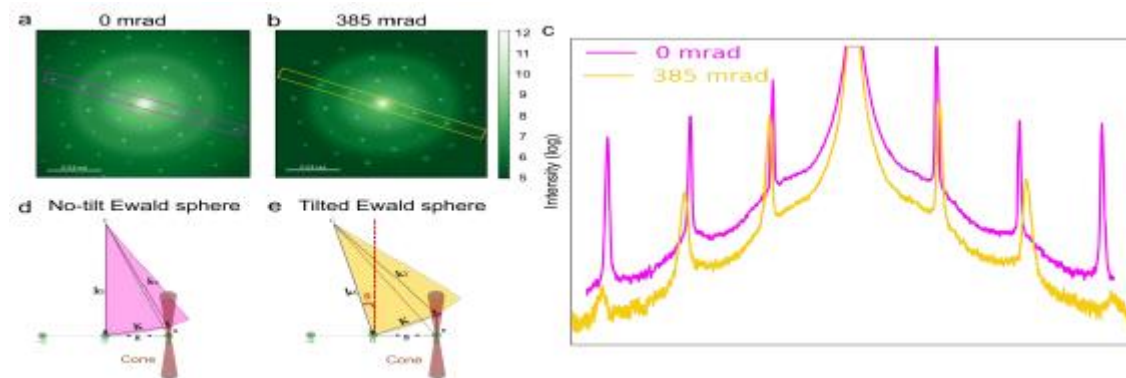


Figure 2. (a) and (b) are the diffraction patterns of a WS₂ monolayer on a 15-nm Si₃N₄ membrane, corresponding to the reciprocal space of a corrugated monolayer and Ewald sphere geometry in (d) and (e). The intensity profiles of the diffraction spots are plotted in (c), which are indicated in (a) and (b) by the purple and yellow box.

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